

Notice of References Cited

Application/Control No. 09/883,922	Applicant(s)/F Reexamination ONO ET AL.	Applicant(s)/Patent Under Reexamination ONO ET AL.	
Examiner	Art Unit		
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U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	4	US-4981549	01-1991	Ichiro et al.	C30B 15/00
	В	US-5817171	10-1998	Sakurada et al.	117/13
	С	US-6120598	09-2000	lida et al.	117/13
	D	US-6179911 B1	01-2001	Tomioka et al.	117/20
	E	US-5935320	08-1999	Graef et al.	117/2
	F	US-6077343	06-2000	lida et al.	117/2
	G	US-6261361 B1	07-2001	lida et al	117/19
	Н	US-6045610	04-2000	Park et al.	117/13
	ł	US-			
	J	US-			
	К	US-			
	L	US-			
	М	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N	EP0962557	12-1999	EPO	lida et al.	C30B 15/00
	0	EP0909840	04-1999	EPO	lida et al.	C30B 15/00
	Р	EP0747513 A2	12-1996	EPO	Takano et al.	C30B 15/00
	Q	EP0716168 A1	06-1996	EPO	Takano et al.	C30B 15/00
	R	EP0890662	01-1999	EPO	lida et al	C30B 15/00
	s					
	Т	,				

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)			
	U	Wolf et al.,. Silicon Processing for the VLSI Era, Volume 1: Process Technology, Lattice Press, Sunset Beach, CA, USA, pp. 8-11, 27-33, 36-72, 124, 139-142, 1986.			
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	W.				
	х				

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).) Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.